

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of) Confirmation No. 4499
Inventor(s): Li Yao et al.)
Appln. No.: 10/689,043) Group Art Unit: 1792
Filed: October 21, 2003) Examiner: ALANKO, A. K.
For: Abrasive-Free chemical mechanical polishing composition and polishing process containing same)))

RESPONSE UNDER 37 C.F.R. §1.111

U.S. Patent and Trademark Office Randolph Building 401 Dulany Street Alexandria, Virginia 22314 MAIL STOP – AMENDMENT

Sir:

In response to the non-Final Office Action mailed on November 29, 2007, the time for responding to which has been extended by the concurrent filing of a two (2) month extension of time, please amend the above application as follows:

Amendment to the claims begins on page 2 of this paper; and Remarks begin on page 7 of this paper.